Amendments to the Specification

Please rewrite paragraph [015] to read as follows:

[0150] The CMP equipment 30 also includes a cleaning solution supply unit. The unit includes one or more cleaning solution supply lines 32 disposed beside the table 12. The cleaning solution supply line 32 is equipped with a spray nozzle 34. The spray nozzle 34 is oriented to spray cleaning solution flowing through the line 32 onto the polishing pad 14 and/or onto the components of the CMP equipment described above. The cleaning solution supply unit also includes a flow regulator 36 and a control valve (not shown) are disposed on the cleaning solution supply line 32 to control the pressure of the cleaning solution fed to the spray nozzle 34, and hence, the pressure of the spray, in response to a control signal applied from a controller (not shown).